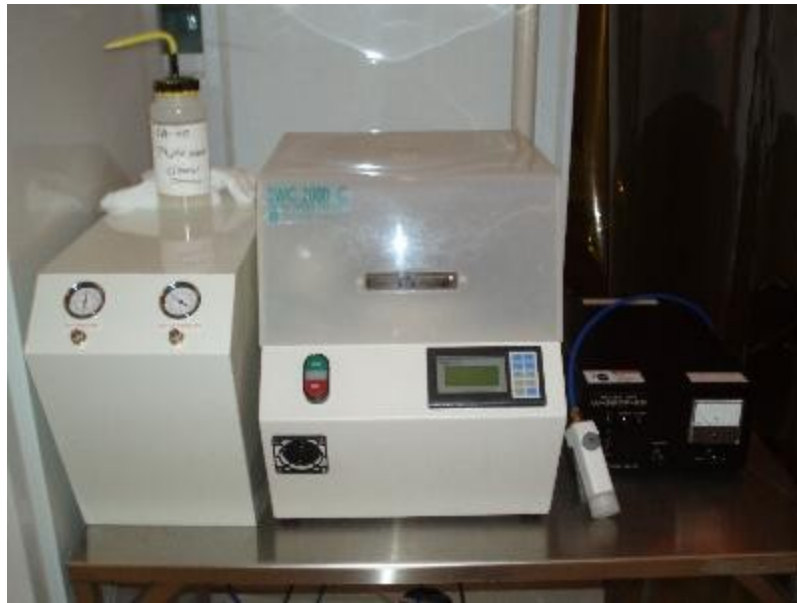




PHOTOMASK CLEANING STATION



LOCATION: WET AISLE 1

PRIMARY TRAINER: Jolene Chorzempa (2-4823, jolenec@ualberta.ca)

SECONDARY TRAINER: Stephanie Bozic (2-6724, sbozic@ualberta.ca)

1. OVERVIEW

Cleaning station for 5inch Soda Lime optical masks. Soap and DI water wash for removal of photo resist and particles after use.

2. SAFETY PRECAUTIONS

If you are bringing any new materials into the NanoFab for use in your process, it is necessary to fill out a chemical import form (available on our website, <http://www.nanofab.ualberta.ca>) and supply an MSDS data sheet to Stephanie Bozic.

3. PROCESS COMPONENTS OR FEATURES

The most effective time to clean the optical masks with this tool is immediately after use in Optical Lithography.



4. OPERATING INSTRUCTIONS

- a) Turn on power switch (underneath power cord on back of spinner)
- b) Open lid and adjust arm. Arm can be unlocked by pressing the yellow ARM button on back of spinner. Press again to lock in place at the outside edge of the chuck.
- c) Place mask on the chuck (chrome side up). If needed, there is a squeeze bottle of Photomask cleaner and optical wipes beside the spinner.
- d) Close lid and press the green START button. The entire cycle is automatic from this point.
- e) The mask cleaning station will beep until the DI water spray turns on. The DI water will turn on and the beeping will stop.
- f) Beeping will begin again once the drying cycle starts. The beeping will stop when the mask is dry.
- g) Open lid and remove mask. There is a nitrogen gun next to the station to remove the little bit of water that may remain on the back.
- h) Place a second mask in the chuck and press START or turn off the power switch.

5. TROUBLESHOOTING

If you encounter an unexpected error or require assistance please contact the primary or secondary trainer listed above. Should they not be available, please contact any staff member for assistance.

6. APPROVAL

QUALIFIED TRAINER: Jolene Chorzempa
TRAINING COORDINATOR: Stephanie Bozic